

IEEE SW Test Workshop Semiconductor Wafer Test Workshop

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probing@hot temperature a new thermal approach to probing accuracy





Invented for life



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Introduction

- You cannot beat physics
- probing at high temperatures generates a very high amount of heat energy
- main problem is drift of X/Y/Z position
- Detailed explanation of these values and a model to explain these drifts are well known [Berger/Seitz, SWTW 2013]



Present Solutions

Methode	Action	Advantage	Disadvantage
Optical realignment	correcting the drift	very accurate; no investment	time consuming; thermal disbalance while realignment; no control between realignments
Pre soaking	accelerates reaching a balanced situation	no investment	time consuming;
Pre-heating of probecard and / or headplate	accelerates reaching a balanced situation	faster than just soaking; not only probecard effected	time consuming; static, non local solution; cost of invest
mathematical prediction	Contol of position by temperature sensors an math. methodes	Local, no time loss	uncertainty remains (no controlling, no monitoring)



Present Solutions

Methode	Action	Advantage	Disadvantage
Passive shielding	prevents heat soaking for a certain time	few investment	Static, non local; retarding but not solving
Cooling of probe card	prevent heat soaking of probecard	Instant effect, no time lost; high invest	Static, non local
"thermal design" of probecard	Fit the design to high temperature use	Intrinsic solution, no other countermeasures	compromise to other PC features; expensive materials; high invest



Measurement of Temperature and Displacement





time (min)

Process of Temperature

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-100

Measurement of Temperature and Displacement

Process of Temperature





Measurement of Temperature and Displacement

Process of Displacement





Temperature Measurement w/o DTS



Temperature distribution on Probecard with +165°C Chuck at rear position

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Temperature Measurement w/o DTS



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95.4°C

20.6°C

Chuck Position

Temperature Measurement w DTS



Temperature distribution on Probecard with +165°C Chuck at rear position

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Temperature Measurement w DTS



Temperature distribution on Probecard with +165°C Chuck center position (no delay)

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Feedback of dynamic thermal shielding (DTS) to wafer

 $T(chuck) = 175^{\circ}C$





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static



PC with DTS at 175°C Testing Temperature



Number of realignments necessary:

Dimension	Probecard w/o cool shield	Probecard w cool shield	· .
Х	23	3	
Y	14	6	
Z	34	4	
sum	71	13	

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 Thermal stabilizing of ceramic head will result in further improvement

 Docking of probecard has to be simplified for production



Summary:

 Stable thermal equilibrium reached by cool shield

Accuracy improved by factors

 Especially fast changes of heat source can be completely compensated

 Effort for realignment can be reduced dramatically

